	P	PATENT COOPE	RATION TREA	ATY	KEUEIVEL
From the				• .	MAR. 3 0. 2005
INTERNATIONAL SEARC	CHING AUTHO	DRITY	•	PCT	OHTSUKA PAT
To: OHTSUKA, YAS	UNORI	·			
7th FL., SHU BLDG., 3-6, KU, Tokyo, 1 JAPAN	KIOICHO,			RITTEN OPINION OI IONAL SEARCHING (PCT Rule 43 <i>bis</i> .1)	AUTHORITY
			Date of mailing (day/month/year)	00 03 20	
			(uuy/mo/u/uyeu/)	29.03.20	03
Applicant's or agent's file P204 - 0466W			FOR FURTHER A	ACTION See paragraph 2 below	
International application 1 PCT/JP2004/		International filing date 14.12.		Priority date (day/mon. 26.12	
International Patent Class Int.Cl 7 H01L21/		or both national classific 7/12, H01L21/		762,H01L29/7	86
Applicant CANON KABUS	SHIKI K	AISHA			
1 This opinion contains	s indications rel	ating to the following ite	ms.		
Box No. I	Basis of the o			·	
Box No. II	Priority	,			
Box No. III	<u>-</u>	ment of opinion with reg	ard to novelty, invent	ive step and industrial a	pplicability
Box No. IV	Lack of unity				
Box No. V	Reasoned state citations and e	ement under Rule 43bis.1(explanations supporting s	a)(i) with regard to not such statement	velty, inventive step or in	dustrial applicability;
Box No. VI	Certain docum	nents cited			
Box No. VII	Certain defect	s in the international app	olication		
Box No. VIII	Certain observ	vations on the internation	al application		<i>:</i>
		•			•
International Prelimir other than this one to opinions of this Inter If this opinion is, as p a written reply togeth	rnational prelimary Examining be the IPEA armational Search provided above, er, where appro	ninary examination is material Authority ("IPEA") excend the chosen IPEA has make a without the considered to be a writter priate, with amendments, and 22 months from the p	pt that this does not ap notified the Internation se so considered. n opinion of the IPEA, before the expiration	oply where the applicant all Bureau under Rule 600 the applicant is invited to 3 months from the date.	chooses an Authority 6.1bis(b) that written to submit to the IPEA
For further options, so	-		,	•	

Date of completion of this opinion				
Name and mailing address of the ISA/JP	Authorized officer		9170	
Japan Patent Office	Yoichi Oshima		 	
3-4-3, Kasumigaseki, Chiyoda-ku, Tokyo 100-8915, Japan Telephone No. +81-3-3581-1101 Ext. 676 4				

3. For further details, see notes to Form PCT/ISA/220.

WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.

PCT/JP2004/018981

Box No. I	Basis of the opinion
1 With	gard to the language, this opinion has been established on the basis of the international application in the language in
	was filed, unless otherwise indicated under this item.
	nis opinion has been established on the basis of a translation from the original language into the following language
	, which is the language of a translation furnished for the purposes of international search (under
	ules 12.3 and 23.1(b)).
	·
	gard to any nucleotide and/or amino acid sequence disclosed in the international application and necessary to the invention, this opinion has been established on the basis of:
a tvo	of material
m 9 b	· ·
<u> </u>	a sequence listing table(s) related to the sequence listing
L	table(s) letated to the sequence fishing
b. for	at of material
	in written format
	in computer readable form
	·
c. tim	of filing/furnishing
-	contained in the international application as filed. filed together with the international application in computer readable form.
·	furnished subsequently to this Authority for the purposes of search.
_	
3.	addition, in the case that more than one version or copy of a sequence listing and/or table relating thereto has been
	led or furnished, the required statements that the information in the subsequent or additional copies is identical to that the application as filed or does not go beyond the application as filed, as appropriate, were furnished.
	and approximent the tribut of the go of one the approximent to approximent, and approximent, and approximent to
4. Addi	nal comments:
	•
	·
	·
	·

WRITTEN OPINION OF THE INTERNATIONAL SEARCHING AUTHORITY

International application No.
PCT/JP2004/ 018981

. Statement			
Novelty (N)	Claims	9,15,17,18	YES
•	Claims	1-8,10-14,16,19,20	NO
Inventive step (IS)	Claims	9,15,17,18	YES
	Claims	1-8,10-14,16,19,20	NO
Industrial applicability (IA)	Claims	1-20	YES
	Claims	:	NO

2. Citations and explanations

D1. JP 2003-78118 A(CANON KABUSIKI KAISHA)2003.03.14, (Family: none)

D2. Michael I. Current, et al., 'Atomic-layer Cleaving with SiGe Strain Layers for Fabrication on Si and Ge-rich SOI Device Layers', IEEE International SOI Conference, October 2001, pp.11-12

D3. JP 2003-78140 A(Mitsubishi Material Silicon Corporation) 2003.03.14, (Family: none)

The subject matters of claims 1-8,10-14,16,19,20 do not appear to be novel with respect to D1. D1 shows that a semiconductor substrate ,comprising on the semiconductor substrate, a strained semiconductor layer induced by SiGe and its manufacturing method.

The subject matters of claims 9,15,17,18 do not appear to involve an inventive step in view of D1,D2 and D3 cited in the ISR. The technical feature of the semiconductor substrates with a strain induction layer which serves also as a separation layer, is not disclosed in D1, D2 and D3.